

L Number	Hits	Search Text	DB	Time stamp
1	0	(blanket adj epitaxial adj growth) and (trench or trenches)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:25
2	4	blanket adj epitaxial adj growth	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:27
3	731	(blanket adj epitaxial adj growth) or BEG	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:29
4	4	((blanket adj epitaxial adj growth) or BEG) and (trench or trenches)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:28
5	1	((blanket adj epitaxial adj growth) or BEG) and (photoresist adj mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:28
6	64	mask and ((blanket adj epitaxial adj growth) or BEG)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:29
7	49	(mask and ((blanket adj epitaxial adj growth) or BEG)) and source	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:29
8	2	((mask and ((blanket adj epitaxial adj growth) or BEG)) and source) and epitaxial	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:30
11	25	(((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and silicon and ((selective adj epitaxial adj growth) or (blanket adj epitaxial adj growth))) and substrate) and (remove or removal or removing or removed or etch or etching or etched)) and (trench near3 (align or aligned or alignment or aligning)) and source	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:36
12	0	(((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and silicon and ((blanket adj epitaxial adj growth))) and substrate) and (remove or removal or removing or removed or etch or etching or etched)) and (trench near3 (align or aligned or alignment or aligning)) and source	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:37
13	0	(((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and silicon and ((BEG) or (blanket adj epitaxial adj growth))) and substrate) and (remove or removal or removing or removed or etch or etching or etched)) and (trench near3 (align or aligned or alignment or aligning))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:38

14	731	BEG or (blanket adj epitaxial adj growth)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:38
15	310	(BEG or (blanket adj epitaxial adj growth)) and source	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:38
16	49	((BEG or (blanket adj epitaxial adj growth)) and source) and mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:39
17	12	((((BEG or (blanket adj epitaxial adj growth)) and source) and mask) and selective	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:39
18	2	(((((BEG or (blanket adj epitaxial adj growth)) and source) and mask) and selective) and (selective near4 (etch or etched or etching))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:41
19	26438	source adj region	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:41
20	223	(source adj region) near3 epitaxial	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:42
21	13	((source adj region) near3 epitaxial) and "p-type region"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:42
22	1	((((source adj region) near3 epitaxial) and "p-type region") and ("p-type region" near4 source)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:44
23	10770	photoresist adj mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:44
24	324	(photoresist adj mask) and "p-type region"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:45
25	137	((photoresist adj mask) and "p-type region") and epitaxial	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:46
26	41	((((photoresist adj mask) and "p-type region") and epitaxial) and (epitaxial near5 (source or p-type))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:56
27	2394005	epitaxial layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:57

28	6006	(epitaxial layer) near5 (source adj region)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:57
29	1397	(epitaxial layer) near5 ("p-type region")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:58
30	95	((epitaxial layer) near5 (source adj region)) and ((epitaxial layer) near5 ("p-type region"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 14:00
31	349	(epitaxial adj layer) near5 (source adj region)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 14:02
32	22	((epitaxial adj layer) near5 (source adj region)) and ("p-type region")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 14:10
33	731	BEG or ("blanket epitaxial growth")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 14:10
34	4	(BEG or ("blanket epitaxial growth")) and trench	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 14:11
35	443455	blanket epitaxial growth	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 14:12
36	4	blanket adj epitaxial adj growth	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 14:12
-	52556	trench or trenches	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 14:26
-	5360	(trench or trenches) and epitaxial	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 14:26
-	5566	(trench or trenches) and (epi or epitaxial)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 14:26
-	3588	((trench or trenches) and (epi or epitaxial)) and (mask or masking)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 14:27
-	214	((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and (protrude or protruding or protruded)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 14:28

-	206	(((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and (protrude or protruding or protruded)) and silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 14:28
-	0	(((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and (protrude or protruding or protruded)) and silicon) and ((selective adj epi adj growth) or (blanket adj epi adj growth))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 14:29
-	3	(((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and (protrude or protruding or protruded)) and silicon) and (SEG or BEG)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 14:31
-	315	((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and silicon and ((selective adj epitaxial adj growth) or (blanket adj epitaxial adj growth))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 14:32
-	311	(((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and silicon and ((selective adj epitaxial adj growth) or (blanket adj epitaxial adj growth))) and substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 14:33
-	311	(((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and silicon and ((selective adj epitaxial adj growth) or (blanket adj epitaxial adj growth))) and substrate) and (remove or removal or removing or removed or etch or etching or etched)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 14:34
-	31	((((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and silicon and ((selective adj epitaxial adj growth) or (blanket adj epitaxial adj growth))) and substrate) and (remove or removal or removing or removed or etch or etching or etched)) and (trench near3 (align or aligned or alignment or aligning))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/04 13:37
-	48	(438/245, 270, "259").ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 15:08
-	0	438/245.ccls	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 15:08
-	1391	438/270.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 15:09
-	48	438/245.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 15:09
-	193	438/259.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 15:47
-	15107	(trench or trenches) and (mask or masking)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 15:47

-	3569	((trench or trenches) and (mask or masking)) and ((selective adj epitaxial adj growth) or (blanket adj epitaxial growth))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 15:49
-	155	((((trench or trenches) and (mask or masking)) and ((selective adj epitaxial adj growth) or (blanket adj epitaxial growth))) and (protuding or protrusion or protrude or protuded)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 15:50
-	14	((((trench or trenches) and (mask or masking)) and ((selective adj epitaxial adj growth) or (blanket adj epitaxial growth))) and (protuding or protrusion or protrude or protuded)) and ((remove or removing or removal or removed) near5 (protrusion or protude or protruded or protruding))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/01 15:52